

NOTES:

1. SUBSTRATE:
FUSED SILICA
2. CENTERING TOLERANCE:
WEDGE: 10±5 ARCMIN
3. COATING (APPLY ACROSS COATING APERTURE)
S1: ULTRAFAST (1000-1060nm)
R(AVG) >99.8% @ 1000 - 1060nm (p-polarization)
R(ABS) >99.9% @ 1030nm (typical, p-polarization)
AT 5° AOI

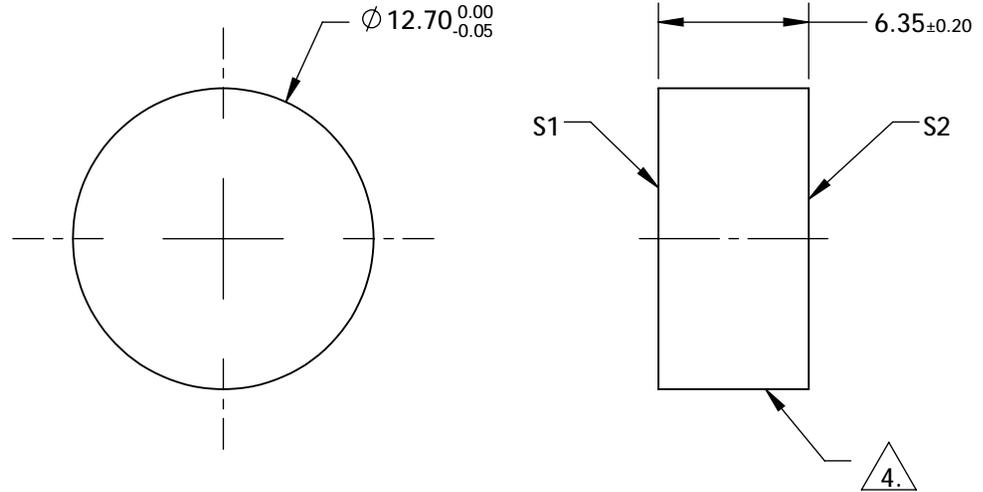
S2: NONE

GROUP DELAY DISPERSION: -500fs²@ 1000 -1060nm

DAMAGE THRESHOLD: 0.3 J/cm² @ 1030nm, 50fs, 1kHz, 100µm BEAM DIAMETER

4. FINE GROUND SURFACE

5. RoHS COMPLIANT



**FOR INFORMATION ONLY:
DO NOT MANUFACTURE
PARTS TO THIS DRAWING**

SPECIFICATIONS SUBJECT TO CHANGE WITHOUT NOTICE
DIMENSIONS ARE FOR REFERENCE ONLY

EO® Edmund Optics®

	S1	S2
SHAPE	PLANO	PLANO
CLEAR APERTURE	80%	N/A
IRREGULARITY (P-V) @ 632.8nm	λ/10	N/A
BEVEL	PROTECTIVE AS NEEDED	PROTECTIVE AS NEEDED

THIRD ANGLE PROJECTION

ALL DIMS IN mm

TITLE

12.7mm 5°, 1030nm HIGHLY-DISPERSIVE
ULTRAFAST MIRROR

DWG NO

12332

SHEET
1 OF 1